Resource Summary Report

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Texas State University PEALD System

RRID:SCR_028201
Type: Tool

Proper Citation

Texas State University PEALD System (RRID:SCR_028201)

Resource Information

URL: https://sro.txst.edu/sro-facilities/sro-nrsc/sro-nrsc-peald.html

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Description: Facility plasma-enhanced atomic layer deposition (PEALD) system from Arradiance utilizes high-speed pulse valves to sequentially deliver reactants that combine to deposit thin films on the surface of a sample at temperatures up to 300C. Eight precursor positions (4 metalorganic + 4 oxidizer) and three plasma gases (N2, O2, H2) enable a wide range of films and process optimization. Plasma-enhanced atomic layer deposition system used for conformal, atomic-scale thin film growth with excellent uniformity and thickness control.

Synonyms: PEALD System (FlexAL-PEALD)

Resource Type: instrument resource

Keywords: PEALD, atomic layer deposition, thin films, plasma deposition, conformal coating,

Availability: Restricted

Resource Name: Texas State University PEALD System

Resource ID: SCR_028201

Alternate URLs: https://sro.txst.edu/sro-facilities/sro-nrsc.html, https://www.sharedinstrumentation.ucsb.edu/instruments/nanotech-nanofabrication-facility/multi-wafer-evaporator

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Ratings and Alerts

No rating or validation information has been found for Texas State University PEALD System.

No alerts have been found for Texas State University PEALD System.

Data and Source Information

Source: SciCrunch Registry

Usage and Citation Metrics

We have not found any literature mentions for this resource.